

A1
encircle

expected number of commercial Extreme Ultraviolet Lithography (EUVL) steppers that will be needed.--

On page 8, lines 2-4, please replace the sentence:

A2
"The thickness of the figure-correcting layer is locally measured and the desired thickness is obtained from the PSDI measurement." with the sentence: --The thickness of the figure-correcting layer is locally measured and the desired thickness is obtained from the phase shifting diffraction interferometer (PSDI) measurement.--

On page 11, lines 7-8, please replace the sentence:

A3
"One could embed the materials by ion implantation or by vacuum deposition." with the sentence: --One could imbed the materials by ion implantation or by vacuum deposition.--

On page 11, lines 11-13, please replace the sentence:

A4
"No additional marking layer is required for the case that a figure correcting film of a different material is added after measuring the figure of the substrate." with the sentence: --No additional marking layer is required for the case in which a figure correcting film of a different material is added after measuring the figure of the substrate.--

Please move the paragraph on page 12, lines 10-21, which states:

A5
"Thin films have been used in the past to correct the figure of mirrors by depositing thin films of the desired thickness profile on top of a substrate using evaporation masks. See W. C. Sweatt, J. W. Weed, A. V. Farnsworth, M. E. Warren, M. E. Neumann, R. S. Goeke, and R. N. Shagan, "Improving The Figure Of Very Good Mirrors By Deposition," OSA Trends in Optics and Photonics Vol.4, "Extreme Ultraviolet Lithography", G. Kubiak and D. Kania, Eds. Washington, DC, Optical Soc. Of

A.S. 2000
America, 1996., pp. 149-155. See also C. Tarrio, E. Spiller, C. J. Evans, T. B. Lucatorto, and C. C. V, "Post-Polish Figuring Of Optical Surfaces Using Multilayer

Deposition," *ibid.*, pp. 144-148. However, it is time consuming and requires many iterations to produce the masks for general corrections in 2-D that is described by higher order polynomials." to page 5, line 21, after the sentence ending with the word "optics".

On page 14, line 20, through page 15, line 2, please replace the sentence:

A.S. 2000
"The modification is accomplished an electron, ion, or photon induced deposition or etching process 24, and the thickness is monitored with an optical monitor 26." with the sentence: -- The modification is accomplished through an electron, ion, or photon induced deposition or etching process 24, and the thickness is monitored with an optical monitor 26.--

In the Claims:

Please amend claims 1 and 23 as follows:

A.S. 2000
1. (Amended) A method for correcting the figure of a substrate, comprising:

measuring the figure of a surface of said substrate;
attaching a figure-correcting layer to a surface of said substrate;
locally adjusting the thickness of said figure-correcting layer; and
measuring the thickness of said figure-correcting layer.